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LENZ, Eric [US/US], 2662 Chocolate Street, Pleasanton, CA 94588 (US).

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(74) Agent: **PETERSON, James, W.**; Burns, Doane, Swecker & Mathis, LLP, P.O. Box 1404, Alexandria, VA 22313-1404 (US).

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(71) Applicant (*for all designated States except US*): **LAM RESEARCH CORPORATION** [US/US], 4650 Cushing Parkway, Fremont, CA 94538 (US)

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(72) Inventors; and

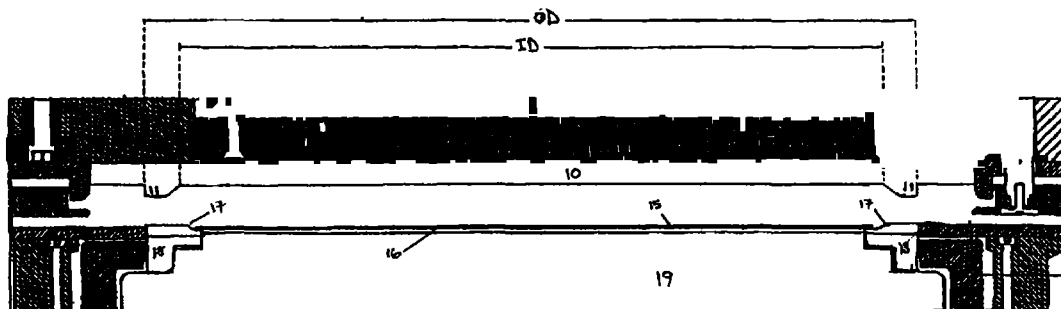
(75) Inventors/Applicants (*for US only*): **DHINDSA, Rajinder** [US/US], 2670 Rollingside Drive, San Jose, CA 95148 (US). **SRINIVASAN, Mukund** [IN/US]; 3836 Springfield Common, Fremont, CA 94555 (US). **EPPLER, Aaron** [US/US], 545 Elm Street, El Cerrito, CA 94530 (US)

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(54) Title: STEPPED UPPER ELECTRODE FOR PLASMA PROCESSING UNIFORMITY



(57) Abstract: A plasma discharge electrode having a front surface with a central portion thereof including gas outlets discharging a process gas which forms a plasma and a peripheral portion substantially surrounding the gas outlets. The peripheral portion has at least one step for controlling a density of the plasma formed by the electrode. The electrode can be used as the grounded upper electrode in a parallel plate plasma processing apparatus such as a plasma etching apparatus. The geometric features of the step and of a corresponding edge ring on the lower electrode can be varied to achieve the desired etch rate profile across a wafer surface.

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